Organotin photoresists for extreme ultraviolet lithography

Zhang, Y.

Link to publication

Creative Commons License (see https://creativecommons.org/use-remix/cc-licenses):
Other

Citation for published version (APA):

General rights
It is not permitted to download or to forward/distribute the text or part of it without the consent of the author(s) and/or copyright holder(s), other than for strictly personal, individual use, unless the work is under an open content license (like Creative Commons).

Disclaimer/Complaints regulations
If you believe that digital publication of certain material infringes any of your rights or (privacy) interests, please let the Library know, stating your reasons. In case of a legitimate complaint, the Library will make the material inaccessible and/or remove it from the website. Please Ask the Library: https://uba.uva.nl/en/contact, or a letter to: Library of the University of Amsterdam, Secretariat, Singel 425, 1012 WP Amsterdam, The Netherlands. You will be contacted as soon as possible.
Publication list

This thesis is based on the following publications:

2. Y. Zhang, J. Haitjema, X. Liu, F. Johansson, A. Lindblad, N. Ottosson, S. Castellanos, A. M. Brouwer, "Influence of thermal process on the chemical reaction and the reaction yield in a model organotin EUV photoresist", Manuscript in preparation. [Chapter 4]

Other publications:


